

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application.

Listing of Claims:

Claim 1 (currently amended)

A measuring system of a gas-stream environment, said measuring system comprises:

a stage, wherein said stage is located on a transport apparatus and used to place a wafer;

a datum platen, wherein said datum platen is located on said transport apparatus and on a side of said stage to be used to place a datum slice;

a lens, wherein said lens is located above said stage to measure said wafer and said datum slice;

a gas supplier, wherein said gas supplier is used to supply a gas;

a first gas nozzle, wherein said first gas nozzle is located on a side of said datum platen;

a second gas nozzle, wherein said second gas nozzle is located on a side of said stage;

a first tube, wherein said first tube is connected with said first gas nozzle and said gas supplier;

a second tube, wherein said second tube is connected with said second gas nozzle and said gas supplier

a transport slot, wherein said transport slot is an opening to exhaust said gas and is used to collect said gas in said gas stream, and used to be a channel to exhaust said gas stream; and

a gas-extracting apparatus, wherein said gas-extracting apparatus connects with said transport slot by using a third tube.

Claim 2 (currently amended)

The system according to claim 1, wherein a first flow rate regulating valve fixed on said first gas nozzle.

Claim 3 (currently amended)

The system according to claim 1, wherein a second flow rate regulating

valve is fixed on said second gas nozzle.

Claim 4 (original)

The system according to claim 1, wherein said gas-extracting apparatus comprises a gas-extracting motor.

Claim 5 (original)

The system according to claim 1, wherein said gas-extracting apparatus comprises a venture structure.

Claim 6 (currently amended)

The system according to claim 1, wherein said gas is an inert gas.

Claim 7 (original)

The system according to claim 1, wherein said gas is nitrogen.

Claim 8 (cancelled)

Claim 9 (currently amended)

A measuring system of a gas-stream environment, said measuring system comprises:

a stage, wherein said stage is located on a transport apparatus and is used to place a wafer;

a datum platen, wherein said datum platen is located on said transport apparatus and on a side of said stage to be used to place a datum slice;

a lens, wherein said lens is located above said stage to measure said wafer and said datum slice;

a gas supplier, wherein said gas supplier is used to supply a gas;

a first gas nozzle, wherein said first gas nozzle is located on a side of said datum platen;

a second gas nozzle, wherein said second gas nozzle is located on a side of said stage;

a first tube, wherein said first tube is connected with said first gas nozzle and said supplier;

a second tube, wherein said second tube is connected with said second gas nozzle and said gas supplier;

a transport slot, wherein said transport slot is an opening; and

a gas-extracting apparatus, wherein said gas-extracting apparatus connects with said transport slot by using a third tube.

Claim 10 (currently amended)

The system according to claim 9, wherein said first tube comprises a first flow rate regulating valve.

Claim 11 (currently amended)

The system according to claim 9, wherein said second tube comprises a second flow rate regulating valve.

Claim 12 (original)

The system according to claim 9, wherein said gas-extracting apparatus comprises a gas-extracting motor.

Claim 13 (original)

The system according to claim 9, wherein said gas-extracting

apparatus comprises a venture structure.

Claim 14(currently amended)

The system according to claim 9, wherein said gas is an inert gas.

Claim 15 (original)

The system according to claim 9, wherein said gas is a nitrogen.

Claim 16 (cancelled)

Claim 17 (currently amended)

A measuring system of a gas-stream environment, said measuring
system comprises:

a stage, wherein said stage is located on a transport apparatus and is
used to place a wafer;

a datum platen, wherein said datum platen is located on said transport
apparatus and on a side of said stage to be used to place a datum slice;

a lens, wherein said lens is located above said stage to measure said

wafer and said datum slice;

a gas supplier, wherein said gas supplier is used to supply a gas in a gas stream;

a first gas nozzle, wherein said first gas nozzle is located on a side of said datum platen and on said transport apparatus to exhaust said gas in said gas stream;

a second gas nozzle, wherein said second gas nozzle is located on a side of said stage and on said transport apparatus to exhaust said gas in said gas stream;

a first tube, wherein said first tube comprises a first flow rate regulating valve, and is connected with said first gas nozzle and said gas supplier;

a second tube, wherein said second tube comprises a second flow rate regulating valve and is connected with said second gas nozzle and said gas supplier;

a transport slot, wherein said transport slot is an opening to exhaust said gas; and

a gas-extracting apparatus, wherein said gas-extracting apparatus connects with said transport slot by using a third tube and is used to produce

an attraction to remove said gas.

Claim 18 (original)

The system according to claim 17, wherein said gas-extracting apparatus comprises a venture structure.

Claim 19 (currently amended)

The system according to claim 17, wherein said gas is an inert gas.

Claim 20 (original)

The system according to claim 17, wherein said gas is nitrogen.

Claim 21 (New)

The system according to claim 1, wherein said first gas nozzle used to exhaust a gas in a gas stream.

Claim 22 (New)

The system according to claim 1, wherein said transport slot used

collect said gas in said gas stream.

Claim 23 (New)

The system according to claim 1, wherein said transport slot used to be
a channel to exhaust said gas in said gas stream.